

Title (en)
LITHOGRAPHY SYSTEM AND PROJECTION METHOD

Title (de)
LITHOGRAPHIESYSTEM UND PROJEKTIONSVERFAHREN

Title (fr)
SYSTEME DE LITHOGRAPHIE ET PROCEDE DE PROJECTION

Publication
EP 1943561 A1 20080716 (EN)

Application
EP 06783923 A 20060914

Priority
• NL 2006000458 W 20060914
• NL 1029973 A 20050916
• US 71785605 P 20050916

Abstract (en)
[origin: WO2007032671A1] The invention relates to a lithography system in which an electronic image pattern is delivered to an exposure tool for projecting an image on a target surface, said exposure tool comprising a control unit for controlling exposure projections, said control unit at least partly being included in the projection space of the said exposure tool, and being provided with control data by means of light signals, said light signals being coupled in to said control unit by using a free space optical interconnect comprising modulated light beams that are emitted to a light sensitive part of said control unit, wherein the modulated light beams are coupled in to said light sensitive part using a holed mirror for on axis incidence of said light beams on said light sensitive part, the hole or, alternatively, holes of said mirror being provided for passage of said exposure projections.

IPC 8 full level
G03F 7/20 (2006.01); **H01J 37/317** (2006.01)

CPC (source: EP KR)
B82Y 10/00 (2013.01 - EP); **B82Y 40/00** (2013.01 - EP); **G03F 7/20** (2013.01 - KR); **G03F 7/70291** (2013.01 - EP); **G03F 7/70525** (2013.01 - EP); **H01J 37/317** (2013.01 - KR); **H01J 37/3177** (2013.01 - EP); **H01J 2237/31774** (2013.01 - EP)

Citation (search report)
See references of WO 2007032671A1

Designated contracting state (EPC)
AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HU IE IS IT LI LT LU LV MC NL PL PT RO SE SI SK TR

DOCDB simple family (publication)
WO 2007032671 A1 20070322; EP 1943561 A1 20080716; JP 2009509329 A 20090305; JP 2012129532 A 20120705; JP 4981806 B2 20120725; JP 5694207 B2 20150401; KR 101367499 B1 20140225; KR 20080047615 A 20080529

DOCDB simple family (application)
NL 2006000458 W 20060914; EP 06783923 A 20060914; JP 2008531037 A 20060914; JP 2012008107 A 20120118; KR 20087009122 A 20060914